

 $\hfill\square$ I_{out} is not accurate as it depends on process, V_{DD} and temperature

 \Box V_{TH} can varies 100mV from wafer to wafer.

□ More severe if the overdrive voltage is lesser in order to consume less headroom. E.g., $V_{GS}=V_{OV}+V_{TH}=200mV+(400mV\pm50mV)$.





If L_{drawn} is doubled, $L_{effective}$ is not as $L_{diffusion}$ is relatively constant.

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MOS as Current Source: $i_{DS} = i$ VDD VDD V MIN VGG Slope = $1/r_{out}$ V_{GG} $v_{DS} = v$ $0 V_{GG}-V_{T0}$ V_{DD}

2 important quantities:

□ R_{out} → 'flatness' of the current sink/source (ideally independent of voltage).

□ V_{MIN} → The minimum output voltage when the current is more constant.





Improve rout and VMIN:

$$V_{MIN} = V_{OV} = \sqrt{\frac{2I_D}{K_N \frac{W}{L}}} = \sqrt{\frac{2.100u}{100u.10}} = 0.426$$

 V_{MIN} =0.1V if W/L=182

Rout can be improved through source-degeneration (cascode configuration)







Example of Cascode Current Sink:



Using the previous parameter (ignore the bulk effect):

 $V_{MIN}=2 V_{DS,sat}=2(0.426)=0.852 \\ R_{out}=g_{m}*r_{ds}*r_{ds}=469u.250K.250K=29.3M\Omega$

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Voltage and Current Reference:

Independent voltage or current source that has a high degree of precision and stability. They should be independent of PVT.

Since most process parameters vary with temperature, if a reference is temperature-independent, then it is usually process independent as well.

The characteristics of bipolar transistors have proven to be the most reproducible and well-defined quantities that can provide positive and negative TC (temperature coefficient).



Negative-TC voltage [3]:

$$\begin{split} I_C &= I_S e^{V_{BE}/V_T}, \text{ where } V_T = \frac{\kappa T}{q} \\ I_S &\propto \mu KT n_i^2, \text{ where } \mu \text{ denotes the mobility of minority carriers and} \\ &n_i \text{ is the intrinsic minority carrier concentration of silicon.} \\ \mu &\propto \mu_o T^m, \text{ where } m \approx -3/2 \\ n_i^2 &\propto T^3 e^{-\frac{Eg}{\kappa T}}, \text{ where } \text{Eg} \approx 1.12 \text{ eV is the bandgap energy of silicon.} \\ \text{Thus, } I_S &= bT^{4+m} e^{-\frac{Eg}{\kappa T}}, \text{ where } b \text{ is a proportionality factor.} \end{split}$$

$$\begin{split} V_{BE} &= V_T ln\left(\frac{I_C}{I_S}\right) \\ \frac{\partial V_{BE}}{\partial T} &= \frac{\partial V_T}{\partial T} ln\left(\frac{I_C}{I_S}\right) - \frac{V_T}{I_S} \frac{\partial I_S}{\partial T}, \text{ assuming } I_c \text{ is constant wrt T.} \\ \frac{\partial I_S}{\partial T} &= b(4+m)T^{3+m}e^{-\frac{Eg}{KT}} + bT^{4+m}\left(e^{-\frac{Eg}{KT}}\right)\left(\frac{Eg}{KT^2}\right) \\ \text{Then, } \frac{\partial V_{BE}}{\partial T} &= \frac{V_{BE} - (4+m)V_T - \frac{Eg}{q}}{T} \end{split}$$

TC of VBE is a function of T. With VBE \approx 750mV and T=300°K, $\frac{\partial V_{BE}}{\partial T} \approx -1.5 mV/^{\circ}K$



Positive-TC Voltage:

Difference between two V_{BE} = PTAT (proportional to absolute temperature).







The ratio can be controlled through current ratio of size ratio.

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 $\Delta V_{BE} = V_T ln(nm)$

 $\frac{\partial \Delta V_{BE}}{\partial T} = \frac{K}{q} \ln(nm)$

Bandgap Reference:



Bandgap reference is derived from V_{BE} (CTAT) and ΔV_{BE} (PTAT). $V_{REF} \approx \alpha_1 V_{BE} + \alpha_2 V_T ln(n)$ At room temperature, $\frac{\partial V_{BE}}{\partial T}$ =-1.5mV/°K and $\frac{\partial V_T}{\partial T}$ =+0.087mV/°K. $V_{REF} \approx V_{BE} + 17.2V_T \approx 1.25V$

Opamp ensures $V_X = V_Y$. ΔV_{BE} drops across R3. I_{PTAT} flows into Q1 and Q2. $V_{OUT} = V_{BE2} + \frac{V_T ln(n)}{R_3} (R_3 + R_2) = V_{BE2} + V_T ln(n) \left(1 + \frac{R_2}{R_3}\right)$ We could choose n=31 and R₂/R₃=4.

TC of resistors will not affect $V_{\mbox{\scriptsize OUT}}$ since ratio is used in the equation.



Bandgap Reference: Collector Current Variation

- $\Box \quad I_{PTAT} \text{ flows into Q1 and Q2 (previous slide). However, we assume IC is constant when we derived <math>\frac{\partial V_{BE}}{\partial T}$. The effect is $\frac{\partial V_{BE}}{\partial T}$ is slightly less negative than -1.5mV/°K.
- □ R typically has positive-TC.
- □ In practice, accurate simulations (+ accurate models) are necessary to predict the temperature coefficient.





Without additional mask, vertical parasitic pnp BJT is available in CMOS process.





Bandgap voltage exhibits a finite curvature. The TC is typically zero at only one temperature.

Some techniques have been devised to suppress the variation of VREF – curvature correction technique.

Likely result of Bandgap Voltage is shown. At certain temperature, VREF is Gaussian distributed.



PTAT Current:





 $I_{PTAT} = \Delta V_{BE}$ drop across R1

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Typically $g_m \downarrow$ as Temp \uparrow , increasing current (I_{PTAT}) help to compensate the drop of g_m .

$$V_{bandgap} = V_{CTAT} + I_{PTAT}R_2 = V_{CTAT} + \Delta V_{BE}\frac{R_2}{R_1}$$